

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	28	("20020025019" "20020177076" "487 8086" "5194344" "5194346" "5308741" "5384219" "5851704" "5906910" "5908718" "6040892" "6498105" "6522389" "6628372").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/30 13:32
L2	0	(kenvin near4 deusman).inv.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:40
L3	0	(kenvin near4 duesman).inv.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:40
L4	175	(kevin near4 duesman).inv.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:40
L5	9	4 and first adj4 (mask or reticle or pattern\$4) and second adj3 (mask or reticle or pattern\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:41
L6	5	4 and (first adj4 (mask or reticle or pattern\$4) and second adj3 (mask or reticle or pattern\$4)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:42
L7	6	(randal near5 chance).inv. and (second adj3 (mask or reticle or pattern\$4)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:43
L8	28	(((\$4lithograph\$4 or exposure) and (second adj3 (mask or pattern\$4 or reticle)) near6 (dispos\$4 or plac\$4 or position\$4) near5 (between near6 (first adj4 (mask or reticle or pattern\$5) near6 (wafer or substrate or object or photosensitive or support\$4 or stage))))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:47

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L9	18	(((\$4lithograph\$4 or exposure) and (second adj3 (mask or pattern\$4 or reticle)) near6 (dispos\$4 or plac\$4 or position\$4) near5 (between near6 (first adj4 (mask or reticle or pattern\$5) near6 (wafer or substrate or object or photosensitive))))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:58
L10	9	(((\$4lithograph\$4 or exposure) and (light or radiation or beam or ray) and (second adj3 (mask or pattern\$4 or reticle)) near4 (dispos\$4 or plac\$4 or position\$4) near5 ("between" near4 (first adj4 (mask or reticle or pattern\$5) near4 (wafer or substrate))))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:57
L11	4	(((\$4lithograph\$4 or exposure) and (second adj3 (mask or reticle)) near6 (dispos\$4 or plac\$4 or position\$4) near5 (between near6 (first adj4 (mask or reticle) near6 (wafer or substrate or object or photosensitive))))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 14:00
L12	3	(((\$4lithograph\$4 or exposure) and (light or radiation or ray or beam) and (second adj3 (mask or reticle)) near6 (dispos\$4 or plac\$4 or position\$4) near5 (between near6 (first adj4 (mask or reticle) near6 (wafer or substrate or object or photosensitive))))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 14:00